JUN 1 5 2006

TET-PT049

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In the PATENT APPLICATION of:

Ching-Wei Lin

Application No.: 10/767,665

Confirmation No.: 5412

Filed:

January 29, 2004

For: PROCESS FOR FORMING

POLYCRYSTALLINE SILICON LAYER BY

LASER CRYSTALLIZATION

Group:

2813

Examiner:

Stephen W. Smoot

Enter

Not

Do

RESPONSE TO NON-COMPLIANT AMENDMENT PURSUANT TO 37 C.F.R. 1.121

S.W.S.

Mail Stop AF

Commissioner for Patents

17_06 P.O. Box 1450

Alexandria, VA 22313-1450

Sir:

Enclosed is the signed amendment.

Respectfully submitted,

Our File:

Date: June 15, 2006

Ching-Wei Lin

Stephen B. Schott

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SBS/tab